



ISPlasma2021/ IC-PLANTS2021

13th International Symposium on Advanced Plasma Science
and its Applications for Nitrides and Nanomaterials
14th International Conference on Plasma-Nano Technology & Science

March 7-11, 2021
VIRTUAL SYMPOSIUM

Organizing Committee

Chairperson

Masafumi Ito, Meijo University

Vice-Chairperson

Koh Matsumoto, Nagoya University

Noriyasu Ohno, Nagoya University

Yoshimi Watanabe, Nagoya Institute of Technology

Sponsored by : The Japan Society of Applied Physics

Co-Sponsored by : Nagoya University Nagoya Institute of Technology Meijo University
Chubu University

<http://www.isplasma.jp/>

Registration

Advanced Online Registration is required.

	General	Student
Registration Fee : Early Registration (Until Jan 31, 2021)	JPY 45,000	JPY 15,000
Late Registration	JPY 50,000	JPY 20,000
Tutorial Fee : Participant in Main Symposium	JPY 1,000	JPY 1,000
Tutorial Registration Only	JPY 10,000	JPY 3,000

* Refunds cannot be made at any reason.

ISPlasma/IC-PLANTS is a specialized international symposium that brings together about 1,000 world-leading scientists and engineers in Nagoya, Japan to discuss latest researches in the fields of advanced plasma science, its applications for processing and manufacturing of nitrides and nanomaterials, as well as new systems for technology transfers. This symposium will address issues such as global warming, resources and energy problems to which advanced plasma science and its application technologies can greatly contribute. In this symposium biosensing technologies will be also highlighted, because of their increasing importance in healthcare, agri-food and environmental areas. We hope that this symposium will provide an ideal venue for the exchange of new ideas and information, and also support the initiation or further development of international collaborations among those who work in these multidisciplinary fields.

Related Fields

Plasma Science & Technologies

- Plasma Source
- Plasma in Liquid
- Flexible Electronics
- Advanced Plasma Diagnostics
- Thin Film Deposition Process
- Plasma for Nano & Green Technologies
- Modeling & Simulation
- Etching Process

Nitride Semiconductors

- Crystal Growth of GaN & Related Materials
- Device Processing
- MBE Growth & Nitrogen Source
- Optical & Optoelectronic Devices
- Characterization
- Electron & Power Devices

Nanomaterials

- Nanodots & Nanoparticles
- 2D Materials
- Composites & Functionally Graded Materials
- Applications for Energy & Environment
- Nanotubes, Nanowires & Nanorods
- Porous Materials & Membranes
- Surface Modification & Functionalization
- Nanomedicine & Sensing

Bio Applications

- Plasma Biology & Medicine
- Biomaterials
- Bioimaging
- Biosensors
- Plasma Agriculture
- Biomarkers
- Biodevices, uTAS, Lab on a Chip
- Device Fabrication Technologies

Abstract Submission

Online abstract submission (one-page English) is available from <http://www.isplasma.jp/>
Submission Deadline : Friday, October 16, 2020 JST

Special Issue

Selected papers will be published in a special issue of a scientific journal.

Tutorial

Tutorial for Plasma Science, Nitride Semiconductors Nanomaterials and Bio Applications will be held.

Contact

Secretariat : Inter Group Corp.

E-mail : isplasma2021@intergroup.co.jp Website : <http://www.isplasma.jp/>

PROGRAM

Plenary Speakers

A. Yoshino (Meijo University, Asahi Kasei Corp., JAPAN)

Keynote Speakers

J.P. Booth (CNRS at LPP, FRANCE)

M. Fujii (Kobe University, JAPAN)

T. Kachi (Nagoya University, JAPAN)

S. Toyokuni (Nagoya University, JAPAN)

Invited Speakers

P. J. Bruggeman (University of Minnesota, USA)

D. Boonyawan (Chiang Mai University, THAILAND)

E. H. Choi (Kwangju University, KOREA)

S. Graham (Georgia Institute of Technology, USA)

M. Hori (Nagoya University, JAPAN)

K. Ide (Tokyo Institute of Technology, JAPAN)

T. Kaneko (Tohoku University, JAPAN)

M. Keidar (The George Washington University, USA)

A. Kohno (Fukuoka University, JAPAN)

Y. Koide (National Institute for Materials Science, JAPAN)

S. Konstantinidis (University of Mons, BELGIUM)

J. S. Kwon (Yonsei University College of Dentistry, KOREA)

Y. Lin (National Synchrotron Radiation Research Center, TAIWAN)

B. Locke (Florida State University, USA)

Invited Speakers

G. Muziol (UNIPRESS, POLAND)

K. Nakazato (Nagoya University, JAPAN)

C. Nishigori (Kobe University, JAPAN)

K. Ohkawa (King Abdullah University of Science and Technology, SAUDI ARABIA)

A. Rousseau (LPP, Ecole Polytechnique, FRANCE)

S. Sato (National Institutes for Quantum and Radiological Science and Technology, JAPAN)

H. Shi (Xi'an Jiaotong University, CHINA)

M. Shikida (Hiroshima City University, JAPAN)

T. Takenobu (Nagoya University, JAPAN)

T. Tatsumi (Sony Semiconductor Solutions Corporation, JAPAN)

X. Wang (Peking University, CHINA)

T. von Woedtke (Leibniz Institute for Plasma Science and Technology, INP Greifswald, GERMANY)

H. G. Xing (Cornell University, USA)

X. Zhao (Shenzhen Yick Xin Technology Development, Ltd. Co., CHINA)

Tutorial Speakers

T. P. Chow (Rensselaer Polytechnic Institute, USA)

U. Czarnetzki (Rhein-Universität Bochum, GERMANY)

D. Graves (UC Berkeley, USA)

L. Miao (Guilin University of Electronic Technology, CHINA)